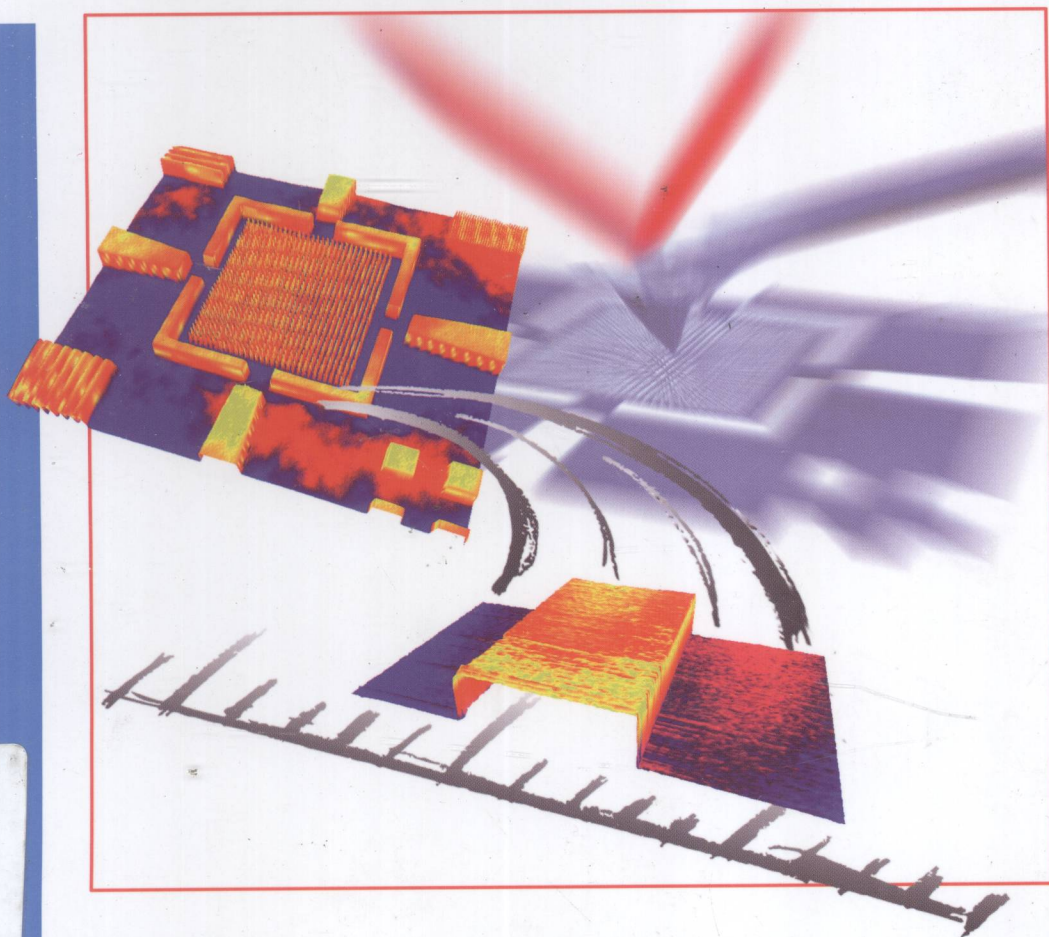


Edited by  
G. Wilkening and L. Koenders

 WILEY-VCH

# Nanoscale Calibration Standards and Methods

Dimensional and Related Measurements in the  
Micro- and Nanometer Range



TB383-53  
N186.4  
2004

# **Nanoscale Calibration Standards and Methods**

Dimensional and Related Measurements  
in the Micro- and Nanometer Range

*Edited by*  
*Günter Wilkening, Ludger Koenders*



WILEY-VCH Verlag GmbH & Co. KGaA

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### **Cover Picture**

Illustration: Hans-Ulrich Danzebrink

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### **Library of Congress Card No.: Applied for British Library Cataloguing-in-Publication Data:**

A catalogue record for this book is available from the British Library.

### **Bibliographic information published by Die Deutsche Bibliothek**

Die Deutsche Bibliothek lists this publication in the Deutsche Nationalbibliografie; detailed bibliographic data is available in the Internet at <<http://dnb.ddb.de>>.

© 2005 WILEY-VCH

Verlag GmbH & Co. KGaA, Weinheim

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**Composition** hagedorn kommunikation,  
Viernheim

**Printing** Strauss GmbH, Mörlenbach

**Bookbinding** J. Schäffer GmbH & Co.,  
Grünstadt

Printed in the Federal Republic of Germany.  
Printed on acid-free paper.

**ISBN-13:** 978-3-527-40502-2

**ISBN-10:** 3-527-40502-X

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and Methods**

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